

PATENT

N1280-00285  
[N1085-00233-TSMC2003-0782]

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application Of: Jhon Jhy Liaw

Examiner: Leigh M. Garbowski

Serial No.: 10/823,822

Group Art Unit: 2825

Filed: 04/15/2004

Confirmation No.: 5620

For: METHOD FOR USING ASYMMETRIC OPC STRUCTURES ON LINE ENDS OF SEMICONDUCTOR PATTERN LAYERS

**NOTICE OF ALLOWANCE**

**Dated: 07/27/2006**

**SUBMISSION OF CORRECTED DRAWINGS**

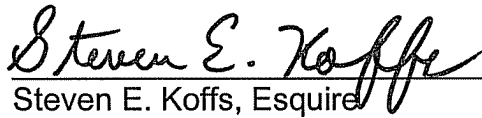
Dear Sir:

Enclosed please find one replacement sheet 1/2 containing corrected Figs. 1A, 1B, 1C. These drawings are being submitted to indicate "(PRIOR ART)" as agreed upon in the Examiner's Amendment.

Please charge any associated underpayment or credit any overpayment to Deposit Account 04-1679.

Respectfully submitted,

Dated: 10-27-06

  
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